

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	(method and different and gate adj oxide and semiconductor and top adj surface and first adj gate adj oxide and hard adj mask and forming and top and first adj layer and polysilicon and soft adj mask and removind adj hard adj mask).clm.	US-PGPUB	OR	ON	2006/08/01 12:41